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(54) Title: ALKALINE, POST PLASMA ETCH/ASH RESIDUE REMOVERS AND PHOTORESIST STRIPPING COMPOSI-
TIONS CONTAINING METAL-HALIDE CORROSION INHIBITORS

(57) Abstract: The invention provides alkaline compositions useful in the microelectronics industry for stripping or cleaning semi-
conductor wafer substrates by removing photoresist residues and other unwanted contaminants. The compositions contain (a) one or
more bases and (b) one or more metal corrosion inhibiting metal halides of the formula: W_zMX_y , where M is a metal selected from
the group Si, Ge, Sn, Pt, P, B, Au, Ir, Os, Cr, Ti, Zr, Rh, Ru, and Sb; X is a halide selected from F, Cl, Br and I; W is selected from
H, to an alkali or alkaline earth metal, and a metal ion-free hydroxide base moiety; y is a numeral of from 4 to 6 depending on the
metal halide; and z is a numeral of 1, 2 or 3.



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